

PATENT  
81839.0107

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Makoto IIDA, et al.

Serial No: 10/009,910

Filed: December 12, 2001

For: SILICON WAFER, SILICON EPITAXIAL  
WAFER, ANNEAL WAFER AND METHOD  
FOR PRODUCING THEM

Art Unit: 1765

Examiner: Matthew J. Song

I hereby certify that this correspondence  
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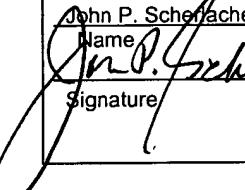
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Commissioner for Patents  
P.O. Box 1450  
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November 2, 2004

Date of Deposit

John P. Scherlacher, Reg. No. 23,009

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Date

**PETITION FOR EXTENSION OF TIME**

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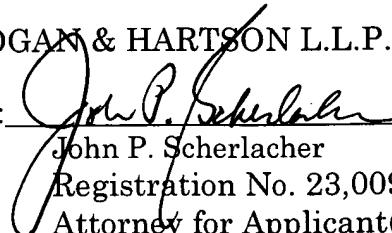
Dear Sir:

In accordance with 37 C.F.R. 1.136, Applicant respectfully petitions the Commissioner for a two-month extension of time extending to November 24, 2004, the period for response to the final Office Action dated June 24, 2004. Please charge the fee of \$430 for this extension to Deposit Account No. 50-1314. The responsive paper(s) are attached.

Please charge any insufficiency or credit any overpayment to Deposit Account No. 50-1314. A copy of this petition is enclosed.

Respectfully submitted,

HOGAN & HARTSON L.L.P.

By: 

John P. Scherlacher  
Registration No. 23,009  
Attorney for Applicant(s)

Date: November 2, 2004

500 South Grand Avenue, Suite 1900  
Los Angeles, California 90071  
Phone: 213-337-6700  
Fax: 213-337-6701

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